

Notice of References Cited	Application/Control No. 10/658,467		Applicant(s)/Patent Under Reexamination OHMI, SHIGEAKI	
	Examiner Jason L. Lazorcik		Art Unit 1731	Page 1 of 1

U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-			
	B	US-			
	C	US-			
	D	US-			
	E	US-			
	F	US-			
	G	US-			
	H	US-			
	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

FOREIGN PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
	O					
	P					
	Q					
	R					
	S					
	T					

NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)			
	U	Anthony, B., Breaux, T., Hsu, S., Banerjee, and A. Tasch, "In situ cleaning of silicon substrate surfaces by remote plasma-excited hydrogen", J. Vac. Sci. Technol. B 7(4), 1989, p621-626			
	V	Vig, J., "UV/Ozone cleaning of surfaces", J. Vac. Sci. Technol. A 3(3), 1985, p1027-1034			
	W	Flamm, D., Donnelly, V., "The Design of Plasma Etchants", Plasma Chemistry and Plasma Processing, 1(4), 1981, p317-363			
	X				

*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.